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# Upper limit for the effect of elastic bending stress on the saturation magnetization of $\text{La}_{0.8}\text{Sr}_{0.2}\text{MnO}_3$

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**The upper limit of effect of elastic bending stress on the saturation magnetization of  $\text{La}_{0.8}\text{Sr}_{0.2}\text{MnO}_3$**

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Using polarized neutron reflectometry (PNR), we measured the influence of elastic bending stress on the magnetization depth profile of a  $\text{La}_{0.8}\text{Sr}_{0.2}\text{MnO}_3$  (LSMO) epitaxial film grown on a  $\text{SrTiO}_3$  (STO) substrate. The elastic bending strain of  $\pm 0.03\%$  has no obvious effect on the magnetization depth profile at saturation. This result is in stark contrast to that of  $(\text{La}_{1-x}\text{Pr}_x)_{1-y}\text{Ca}_y\text{MnO}_3$  (LPCMO) films for which strain of  $\pm 0.01\%$  produced dramatic changes in the magnetization profile and Curie temperature. We attribute the difference between the influence of strain on the saturation magnetization in LSMO (weak or none) and LPCMO (strong) to a difference in the ability of LSMO (weak or none) and LPCMO (strong) to phase separate. Our observation provides an upper limit of tuning LSMO saturation magnetization via elastic strain effect.

## Introduction

Numerous efforts have been made to find magnetoelectric multiferroic (MF) materials that exhibit strong coupling between ferromagnetic (FM) and ferroelectric (FE) order parameters<sup>1,2,3</sup> at room temperature. Such functionality provides intriguing opportunities for next-generation data storage, sensor, and actuator technologies.<sup>4</sup> Coupling of FM and FE order parameters is rare in single phase materials.<sup>5</sup> Exceptions often exhibit weak magnetoelectric coupling at low temperatures. As an alternative to single phase materials, nanocomposites of FM and FE materials show promise. The doped-manganite perovskites, e.g.,  $\text{La}_{1-x}\text{Sr}_x\text{MnO}_3$  (LSMO), have been chosen as one of the best FM materials in MF nanocomposites fabrication due to their superior magnetic properties and the versatile phases at different doping across the phase diagram.<sup>6</sup> Diverse types of LSMO/FE heterostructure, such as LSMO/ $\text{BaTiO}_3$  (BTO),<sup>7</sup> LSMO/ $[\text{Pb}(\text{Mg}_{1/3}\text{Nb}_{2/3})\text{O}_3]_{1-x}[\text{PbTiO}_3]_x$  (PMN-PT),<sup>8,9</sup> and LSMO/ $\text{Pb}(\text{Zr}_{0.2}\text{Ti}_{0.8})\text{O}_3$  (PZT),<sup>10,11</sup> have been grown and extensively studied to realize the magnetoelectric couplings and different mechanisms have been proposed. Changes of ordering temperature and (near) remanent magnetization of LSMO films have been documented in LSMO/BTO heterostructures during BTO phase transformation<sup>7</sup> and in LSMO/PMN-PT heterostructures as responding to the external electric field,<sup>8,9</sup> and have been attributed to the strain effects. More recently, the magnetic properties of LSMO films were observed to be affected by proximity to PZT and have been attributed to hole accumulation or depletion at LSMO/PZT interface caused by the change of PZT polarization under different electric field rather than strain.<sup>10,11</sup>

In general, the change of polarization in FE materials is always associated with crystal distortion. Thus in LSMO/FE heterostructures, one should not exclude strain as a contributing factor influencing the interfaced LSMO magnetic properties when applying electric field across FE. In order to distinguish between these two mechanisms, we examined the influence of applied elastic bending stress on the magnetization of  $\text{La}_{0.8}\text{Sr}_{0.2}\text{MnO}_3$  epitaxial films grown on  $\text{SrTiO}_3$  (STO) using polarized neutron reflectometry (PNR) technique with a four-point bending jig.<sup>12,13</sup> This allowed us to investigate the exclusive role of strain on the LSMO magnetization properties. We found that elastic bending strain of  $\pm 0.03\%$  has no obvious effect on the magnetization depth profile at saturation. This result is in stark contrast to that of  $(\text{La}_{1-x}\text{Pr}_x)_{1-y}\text{Ca}_y\text{MnO}_3$  ( $x \sim 0.60$ ,  $y \sim 0.20$  and  $0.33$ ) (LPCMO) films for which strain of  $\pm 0.01\%$  produced dramatic changes in the magnetization profile and Curie temperature.<sup>12,13</sup> We further attribute the difference between the influence of strain on the saturation magnetization in LSMO (weak or none) and LPCMO (strong) to a difference in the ability of LSMO (weak or none) and LPCMO (strong) to phase separate. Our observation provided an upper limit of tuning LSMO saturation magnetization using strain effect and also shed new light on designing functional spintronic devices using strain/charge effect across manganites/FE interfaces. Namely, that strain may be less of a factor influencing magnetism in a manganite/FE heterostructure than other factors, e.g., charge doping.

#### **Sample preparation and chemical characterization**

High quality epitaxial LSMO ( $x = 0.2$ ) films (47 nm) were grown on  $1\text{ cm} \times 1\text{ cm}$  STO (001) substrates (250  $\mu\text{m}$  thick) by pulsed laser deposition (PLD, KrF excimer laser,  $\lambda=248\text{ nm}$ ). The substrate temperature was maintained at  $750\text{ }^\circ\text{C}$ . A low oxygen pressure

of 50 mTorr and low laser repetition rate were used to grow high quality thin films with smooth surfaces.<sup>14</sup> The rectangular laser beam with an area of 5.55 mm<sup>2</sup> was focused onto the target with an energy density of 2 J/cm<sup>2</sup>. An image beam method was used to obtain stabilized and uniform laser energy density on the target.<sup>15</sup> After deposition, films were annealed *in situ* at 600 °C and 500 Torr oxygen for 30 minutes before cooling to room temperature at 5 °C/min. The orientation, thickness and original strain states of films were investigated by high resolution X-ray diffraction (XRD) using PANalytical MRD PRO X-ray diffractometer with the Triple Axis option, as shown in Figures 1(a) and 1(b). The XRD measurements indicated that the LSMO film was epitaxially grown on the STO substrate.

The chemical density profile, including film thickness and roughness was obtained from X-ray reflectometry (XRR). The XRR normalized to the asymptotic value of the Fresnel reflectivity ( $R_F = 16\pi^2/Q^4$ ) is plotted in Figure 1(c) versus wave vector transfer  $Q (= 4\pi \times \sin\theta / \lambda)$ .  $\theta$  is the angle of incidence between the incident wave vector and its projection onto the sample's surface;  $\lambda$  is wavelength. Calculated reflectivities were obtained from a model representing the LSMO film with a bulk region and a very thin ( $\sim 1$  nm) surface region on STO using the Parratt formalism.<sup>16,17</sup> The model was refined to optimize a goodness-of-fit.<sup>18,19</sup> The x-ray scattering length density (SLD) profiles of the model are shown in the inset of Figure 1(c). The model provides values of the surface and interface roughness and layer thicknesses used to constrain the analysis of the PNR data presented later. The existence of the thin surface layer with slightly reduced X-ray SLD could be due to the surface contamination or degradation of the LSMO films at the LSMO/air interface.

Scanning transmission electron microscopy (STEM) and electron energy-loss spectroscopy (EELS) measurements were performed on a thinner (34 nm) LSMO/STO sample, which was grown using the same system and under the same growth conditions. Consistent with the XRD and XRR studies discussed above, The STEM result (Figure 1(d)) indicates excellent epitaxial growth. No noticeable variation of the lattice spacing of LSMO either parallel or perpendicular to the LSMO/STO interface was detected by Fourier analysis of the TEM images, *i.e.*, no evidence for non-uniformity of strain in the film was observed. The EELS imaging indicates the chemical composition of the film bulk to be exceedingly uniform (Figure 1(e)). The chemistry of the surface is more ambiguous due to electron beam broadening effects resulting from dechanneling.

#### **Magnetometry and magnetotransport measurements**

The temperature and field dependence of the magnetization of the 47 nm LSMO films were measured by a superconducting quantum interference device (SQUID) magnetometer. The magnetic field was applied parallel to the film plane. At 50 K, the magnetization in the plane of the sample,  $M$ , taken as a function of field,  $H$ , is shown in Figure 2(a), inset. The magnetization was recorded after cooling in a field of 5 kOe as shown in Figure 2(a), from which a Curie temperature of 317 K was obtained.

For magnetotransport measurements, Au electrodes were patterned on bar shaped thin films (2 mm  $\times$  10 mm). The resistance of LSMO films was measured by standard four-probe method using a physical property measurement system (PPMS). As shown in Figure 2(b), measurements were made under different magnetic field ( $\mu_0 H = 0, 1, 5$ , and 7 T) applied perpendicular to the film plane and for warming and/or cooling cycles. The current was measured across the surface of the film. The heating/cooling rate during data

collection was 2 K/min, and the sample had been thermally demagnetized before the measurements. The magnetotransport curves show the magnetoresistance effect and metal-insulator transition (MIT) with  $T_c \sim 315$  K at zero field and increasing with magnetic fields. Furthermore, under 0 T and 1 T field no hysteresis behavior was observed in the transport during cooling/warming cycles, thus, we see no evidence for phase separation which usually gives rise to hysteresis as was the case for LPCMO thin films.<sup>12,13</sup> Here we also note that for the magnetoresistance measurement, the direction of the applied field is perpendicular to the film instead of within the film, which is determined by the available experimental setup of the instrument. Though the missing of the resistance hysteresis is a universal behavior and independent to the applied field direction.<sup>20</sup>

#### **PNR study on bending sample**

Bending stress was applied to the 47 nm LSMO film using a four-point bending jig in the method described in Ref. 1. Depending upon the orientation of the film with respect to the jaws of the bending jig, compressive or tensile bending stress can be applied, as indicated in the insets of Figures 3(a) and 3(c). The radius of curvature of the sample was oriented normal to the scattering plane of the neutron experiment so that the bent sample did not affect the width of the specularly reflected neutron beam. The PNR result (Figures 3(a)-3(c)) was obtained using the Asterix spectrometer at the Los Alamos Neutron Science Center.<sup>21</sup> The sample was cooled to 10 K in a field of  $H = 5$  kOe and measured in this field. The reflectivities were measured for bending strains of  $\epsilon = -0.03\%$  (compression),  $\epsilon = 0$  and  $\epsilon = +0.03\%$  (tension). The bending strain of the film was measured using<sup>22</sup>  $\epsilon = t_s/R$ , where  $t_s$  and  $R$  are the thickness of substrate and the radius

of the curvature of the film, respectively. The radius of curvature of the sample was measured with a laser.<sup>23</sup>

The specular reflectivity,  $R$ , is determined by the neutron scattering length density (SLD) depth profile,  $\rho(z)$ , averaged over the lateral dimensions of the sample.

$\rho(z)$  consists of nuclear and magnetic SLDs such that  $\rho^\pm(z) = \rho_n(z) \pm CM(z)$ , where  $C = 2.91 \times 10^{-9} \text{ \AA}^{-2} (\text{kA/m})^{-1}$  and  $M(z)$  is the magnetization (a moment density obtained in kA/m) depth profile.<sup>21</sup> The  $+$ ( $-$ ) sign denotes neutron beam polarization parallel (opposite) to the applied field and corresponds to reflectivities,  $R^\pm(Q)$ . Thus, by measuring  $R^+(Q)$  and  $R^-(Q)$ ,  $\rho_n(z)$  and  $M(z)$  can be obtained separately. The nuclear SLD and magnetization depth profiles are shown in Figures 3(d) and 3(e). Consistent with the XRD, STEM, and EELS studies, the nuclear SLD exhibits uniform chemical composition throughout the film. Compared with the XRR result which suggested slightly reduced X-ray SLD within the surface region, the obtained magnetization depth profile does suggest reduced magnetization (region I in Figure 3(d)) at the LSMO surface for all strain cases. The reduction could be due to a perturbed electron configuration/distribution at the surface (indicated by the Xray SLD) and/or be sensitive to the surface termination. PNR fits also indicate reduced magnetization at the LSMO/STO interface. This is consistent with neutron scattering experiments of films and superlattices of other groups, which also report a magnetically degraded interface region.<sup>12,24</sup> Magnetic depletion layers at interfaces have been attributed to change of chemistry<sup>12</sup> (though our data indicate this is not the case for our samples), strain, or discontinuity of interface charge. In the present study, our sample is close to uniformly strained (evidence from TEM) in the absence of bending stress. In the bending case, the



magnitude of the variation of the applied bending strain across the thickness of the film is very small; approximately  $4 \times 10^{-4}$  times the bending strain. We note the charge discontinuity across the LSMO/STO interface is  $0.8 e^-$  per lateral unit cell. It is often cited that the charge discontinuity at the interface might cause the depletion layer,<sup>24</sup> though Guo *et al.* recently reported that the charge discontinuity could enhance the magnetization instead.<sup>25</sup>

### **Bending effect on LSMO magnetization**

Returning to the question of what is the influence of elastic bending stress on magnetism of LSMO, suppose the magnetization and elastic strain are coupled in LSMO, the total magnetization on application of strain is then given by  $M^2 = M_0^2 + M_\epsilon^2 = M_0^2 - (Y/\gamma) \times \epsilon$ , where  $Y$  is Young's modulus and  $\gamma$  is the magnetoelastic coefficient.<sup>12</sup> In Figure 4, we show  $M^2$  vs.  $\epsilon$  curves for LSMO bulk and interfacial regions obtained from PNR and fit both with a linear function. Very similar slopes for both lines,  $-Y/\gamma = (0.2 \pm 0.1) \times 10^8 \text{ (kA/m)}^2$ , are obtained. Previously, we examined the role of elastic bending stress on the saturation magnetization and ordering temperature of LPCMO epitaxial films using the same technique.<sup>12,13</sup> Specifically, bending stress yielding very small  $\sim 0.01\%$  compressive strain greatly increased the magnetization by  $\sim 20\%$  and the Curie temperature by  $\sim 5\%$  compared to the case for no applied stress. Applied tensile bending stress of the same magnitude decreased the magnetization and Curie temperature by similar amounts. In Figure 4, we also plot the  $M^2$  vs.  $\epsilon$  results obtained from LPCMO sample for direct comparison. For the LPCMO bulk region,  $-Y/\gamma = -(8 \pm 1) \times 10^8 \text{ (kA/m)}^2$  near the MIT transition temperature  $T_c$  (78 K) and  $-Y/\gamma = -(6 \pm 1) \times 10^8 \text{ (kA/m)}^2$  at a temperature way well below  $T_c$  (20 K) were obtained. Compared to

LPCMO, the saturation magnetization in LSMO has very weak or negligible response to the elastic bending stress for  $\epsilon = \pm 0.03\%$ .

Our magnetotransport measurements on LSMO films show no hysteresis behavior during cooling and warming cycles, in stark contrast to LPCMO films which present a  $\sim 20$  K difference in MIT transition temperature between cooling and warming cycles and suggest the existence of phase separation and competition. The influence of bending stress on the Curie temperature of LPCMO greatly exceeds theoretical predictions for the case of biaxial strain in  $\text{La}_{1-x}\text{Sr}_x\text{MnO}_3$  (LSMO).<sup>26</sup> On the other hand, some theoretical work attributes phase co-existence (or phase separation, phase texture, *etc.*) to a complex landscape consisting of non-linear relationships between strain and rearrangement of the unit cell contents,<sup>27</sup> which suggests LPCMO could be sensitive to stress.<sup>28,29</sup> Thus we conclude from this result that bending stress has a very weak to negligible effect on a system that shows weak or no phase separation (LSMO) compared to one that can be strongly phase separated (LPCMO). This result reinforces the hypothesis that the strain-energy landscape is a crucial factor determining the magnetic properties of materials that phase-separated.

Previously, Lee *et al.*<sup>7</sup> measured the (near) remanent magnetization of 50 nm thick  $\text{La}_{0.67}\text{Sr}_{0.33}\text{MnO}_3$  films grown on  $\text{BaTiO}_3$  (001) substrates. The data were collected as a function of temperature to measure the influence of stress imposed on the film due to the tetragonal (*T*) to monoclinic (*M*) and monoclinic to rhombohedral (*R*) phase transformations. They defined the term  $\epsilon_a = 1/2(\epsilon_{xx} + \epsilon_{yy})$  which is a measure of the in-plane change of area occurring due to a structural phase transformation of the substrate. A positive value of  $\epsilon_a$  results from an expansion or tensile stress. They reported changes

of magnetization to be  $\sim 250\%$  and  $12\%$  for  $T$  to  $M$  ( $\epsilon_a = +0.21\%$ ) and  $M$  to  $R$  ( $\epsilon_a = +0.10\%$ ), respectively. Furthermore, Lee *et al.*<sup>7</sup> reported an *expansion*,  $+\epsilon_a$ , is accompanied by an *increase* of remanent magnetization. This enhancement, below Curie temperature, is mainly attributed to the reversal of magnetic anisotropy due to the structural phase transformation.

Subsequently, Thiele *et al.*<sup>8,9</sup> measured the influence of biaxial strain on the (near) remanent magnetization of 20 to 50 nm thick  $\text{La}_{0.7}\text{Sr}_{0.3}\text{MnO}_3$  thin films grown on PMN-PT (001) FE single crystal substrates. For the case of biaxial strain  $\epsilon_{xx} = \epsilon_{yy}$ ,  $\epsilon_a$  can be obtained. Using data shown in Figure 5 of Ref. 9, a change of  $\epsilon_a = +0.15\%$  produced a change of  $-25\%$  in the remanent magnetization at 330K but no detectable strain effect on the remanent magnetization at low temperatures. Note, Thiele *et al.*<sup>8,9</sup> report *expansion* in-plane strain,  $+\epsilon_a$ , is accompanied by a *decrease* of remanent magnetization.

For the case of bending plate strain as realized in our experiment,  $\epsilon_{yy} = 0$ , so  $\epsilon_a = 0.5 \times (\pm 0.03\%) = \pm 0.015\%$ .<sup>30</sup> (The bending jig enables measurement of magnetism in response to both tensile and compressive strain.) With strain of order  $|\epsilon_a| = 0.015\%$ , no statistically significant change of the LSMO saturation magnetization was observed. The important distinction between our work and the previous studies is that we have measured the influence of stress on the saturation magnetization, while previous work has measured the (near) remanent magnetization. Thus, our experiment is not affected by changes of anisotropy induced by strain. The previous studies used BTO and PMN-PT substrates, both FE's, which could potentially alter the charge of the LSMO/FE interface. In our experiment, we only applied mechanical stress across the sample. The different observations of the studies of Lee *et al.*<sup>7</sup> and Thiele *et al.*<sup>8,9</sup> might be reconciled by

considering both the influence of strain on anisotropy at remanent and the interfacial polarization effect from BTO and PMN-PT, which requires further investigation.

The bending strain applied in our experiment is fully elastic. Considering that the Young's modulus of manganites is in the order of 200 GPa<sup>31</sup> and the yield strength of perovskite ceramic (e.g., SrTiO<sub>3</sub>) is in the order of 120 to 300 MPa,<sup>32</sup> the upper limit of elastic strain of a manganite film is in the order of 0.06% to 0.15%. If we choose 0.15% as the upper limit of elastic strain and assume the linear relation between  $M^2$  and  $\epsilon$  persists within the full range, the maximum change of the saturation magnetization of LSMO due to the elastic strain effect is less than 10%. To further test our result and to even explore the influence of the inelastic strain on the LSMO film's magnetization, additional experiments are needed which could achieve higher strain without introducing extra degree of freedom, e.g., using pressure cell for PNR experiment.

## **Conclusions**

In conclusion, we have measured the magnetization depth profile across a LSMO ( $x = 0.2$ ) epitaxial film epitaxially grown on (001) STO. The neutron measurements were performed as a function of applied elastic bending stress. With bending strain  $\epsilon = \pm 0.03\%$ , no obvious influence of strain on the LSMO saturation magnetization depth profile was observed, this is very different from the previously studied LPCMO films. We attribute the difference between the influence of strain on the saturation magnetization in LSMO (weak or none) and LPCMO (strong) to a difference in the tendency of LSMO (weak or none) and LPCMO (strong) to phase separate. The upper limit of tuning LSMO saturation magnetization using elastic strain is also discussed.

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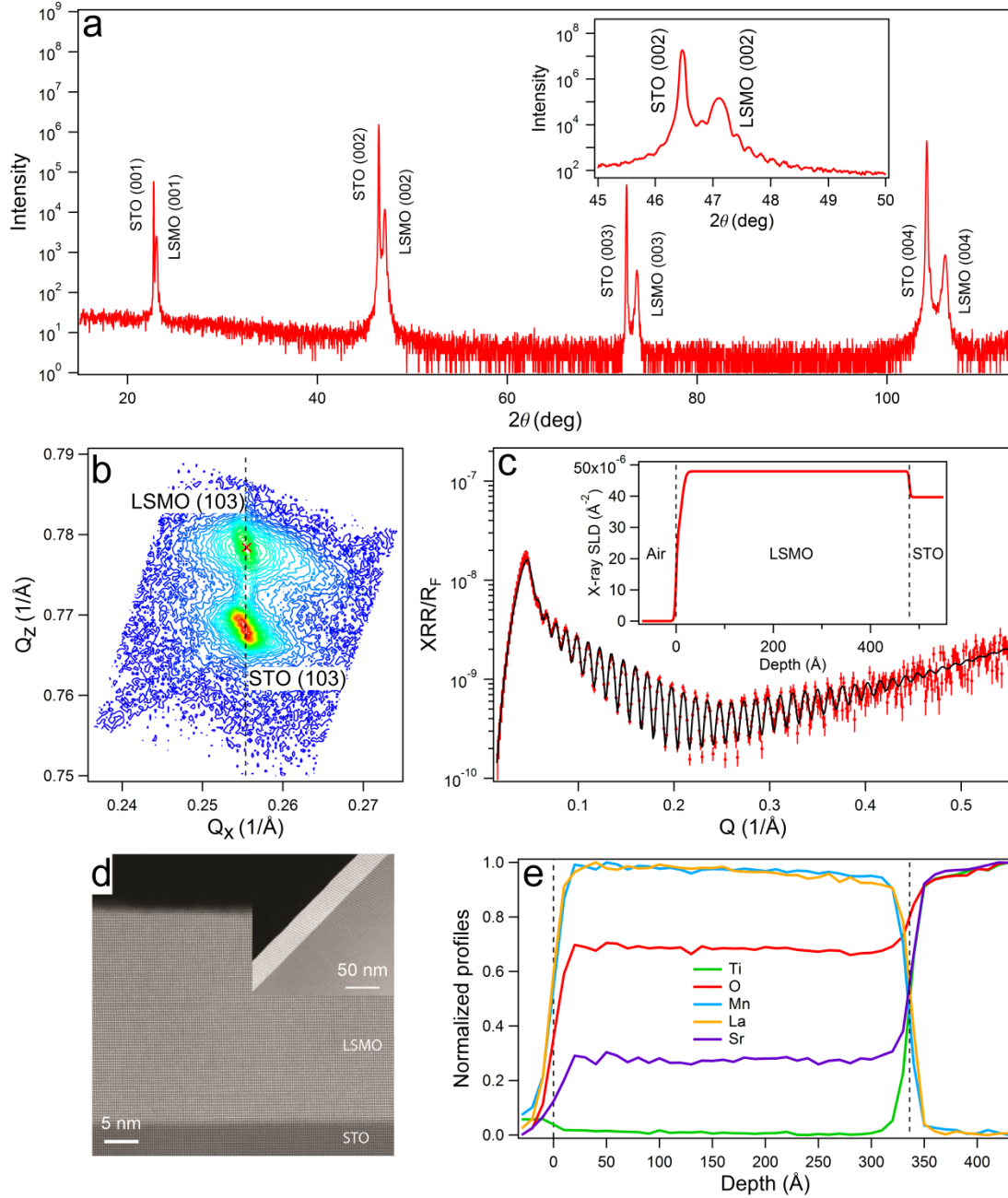


Figure 1. (a) X-ray diffraction  $\theta/2\theta$  scan for LSMO/STO film. Inset:  $\theta/2\theta$  scan around STO (002) and LSMO (002) peaks. (b) Reciprocal space map around STO (103) and LSMO (103) reflections. (c) X-ray reflectivity curve normalized to  $R_F$  and the corresponding fit for LSMO/STO film. Inset: X-ray scattering length density depth profile obtained from the best fit. (d) STEM Z-contrast image of a thinner (34 nm) LSMO/STO film sample taken down the (110) zone axis. Inset: A low magnification image. (e) Normalized, integrated EELS profiles measured along the growth direction obtained from the from the Ti  $L_{2,3}$ , O K, Mn  $L_{2,3}$  La  $M_{4,5}$  and Sr  $L_{2,3}$  absorption edges. Data acquired in a Nion UltraSTEM200, operated at 200 kV, equipped with a fifth order aberration corrector and a Gatan Enfium spectrometer.

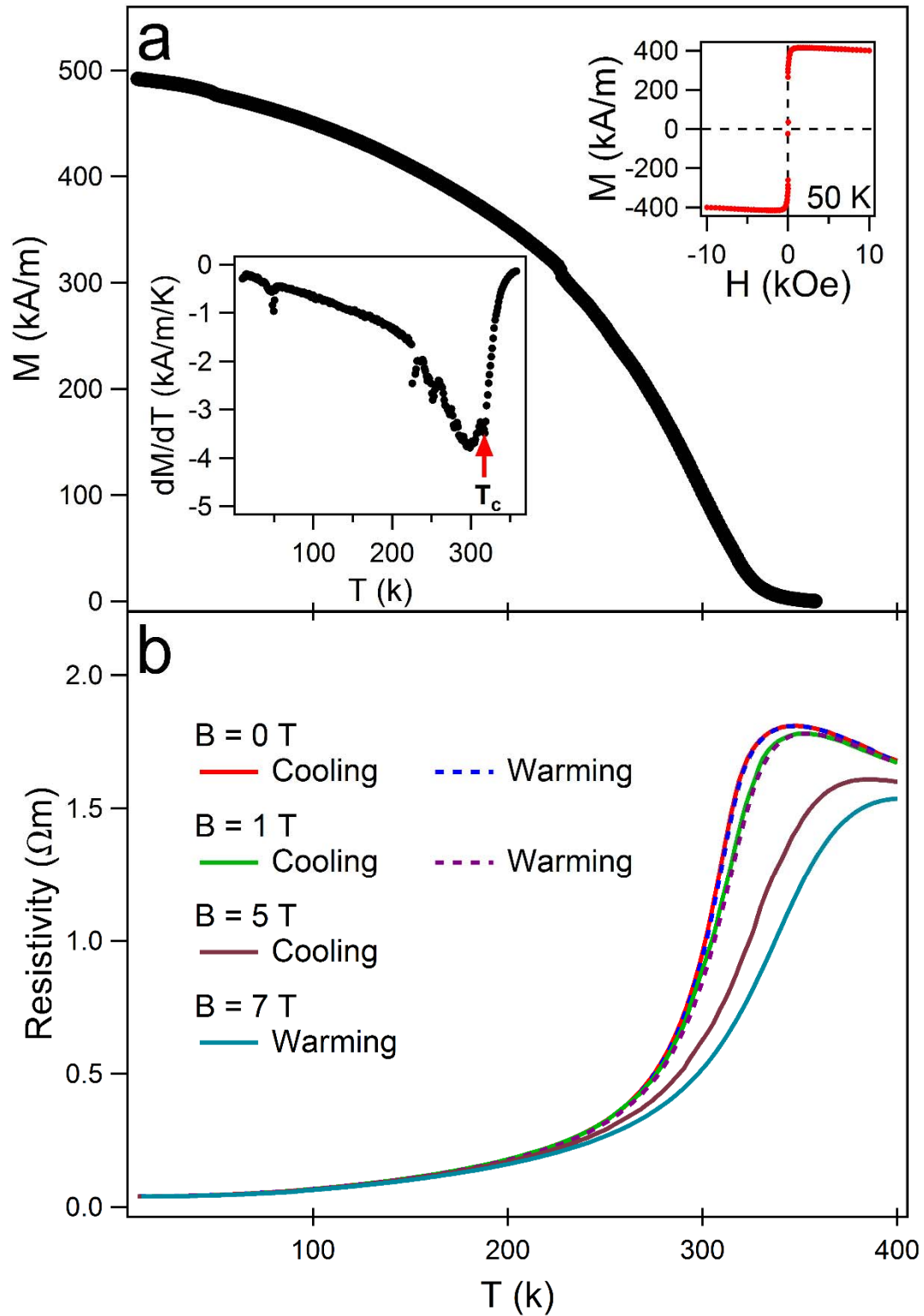


Figure 2. (a) Temperature dependence of the magnetization. Lower inset: the corresponding derivative curve. Upper inset: M-H curve at 50K and  $\pm 10$  kOe. (b) Temperature dependence of the resistivity at different thermal and field conditions.

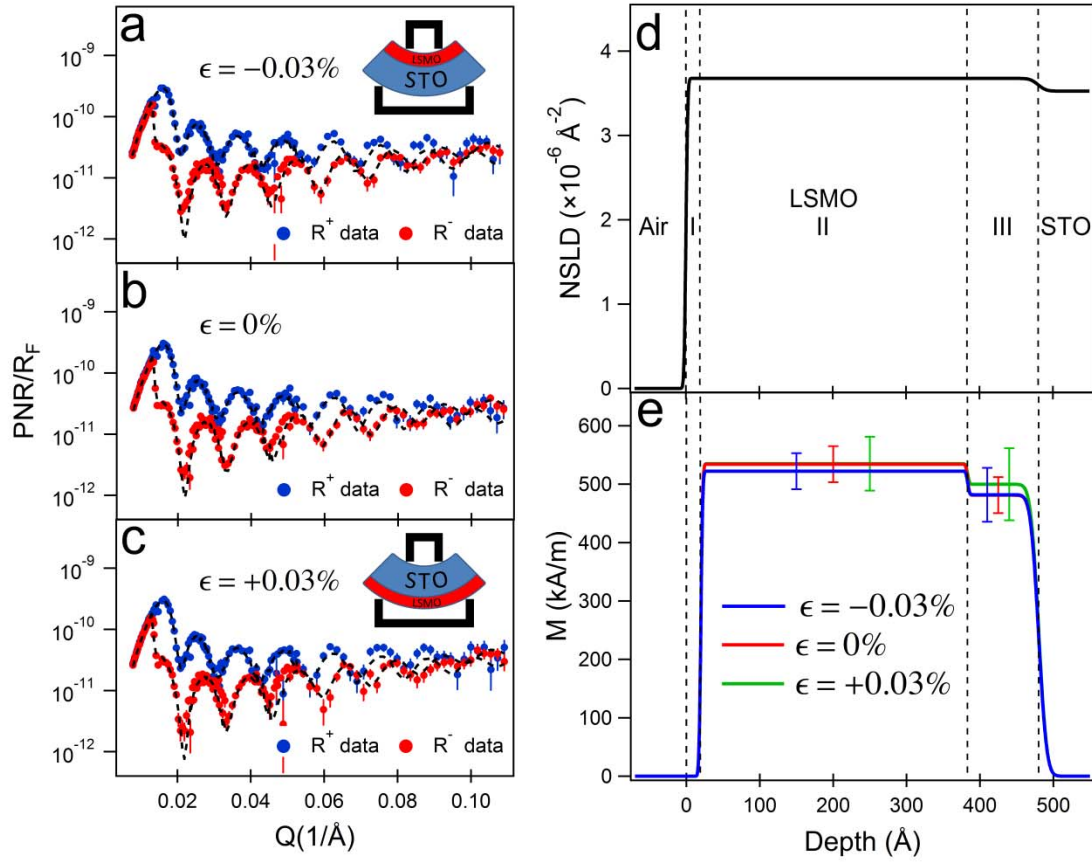


Figure 3. (a)-(c) Polarized neutron reflectivity normalized to  $R_F$  for three values of bending strain and the corresponding fits. (d) Obtained nuclear scattering length density depth profile. (e) Obtained magnetization depth profiles for three bending cases.



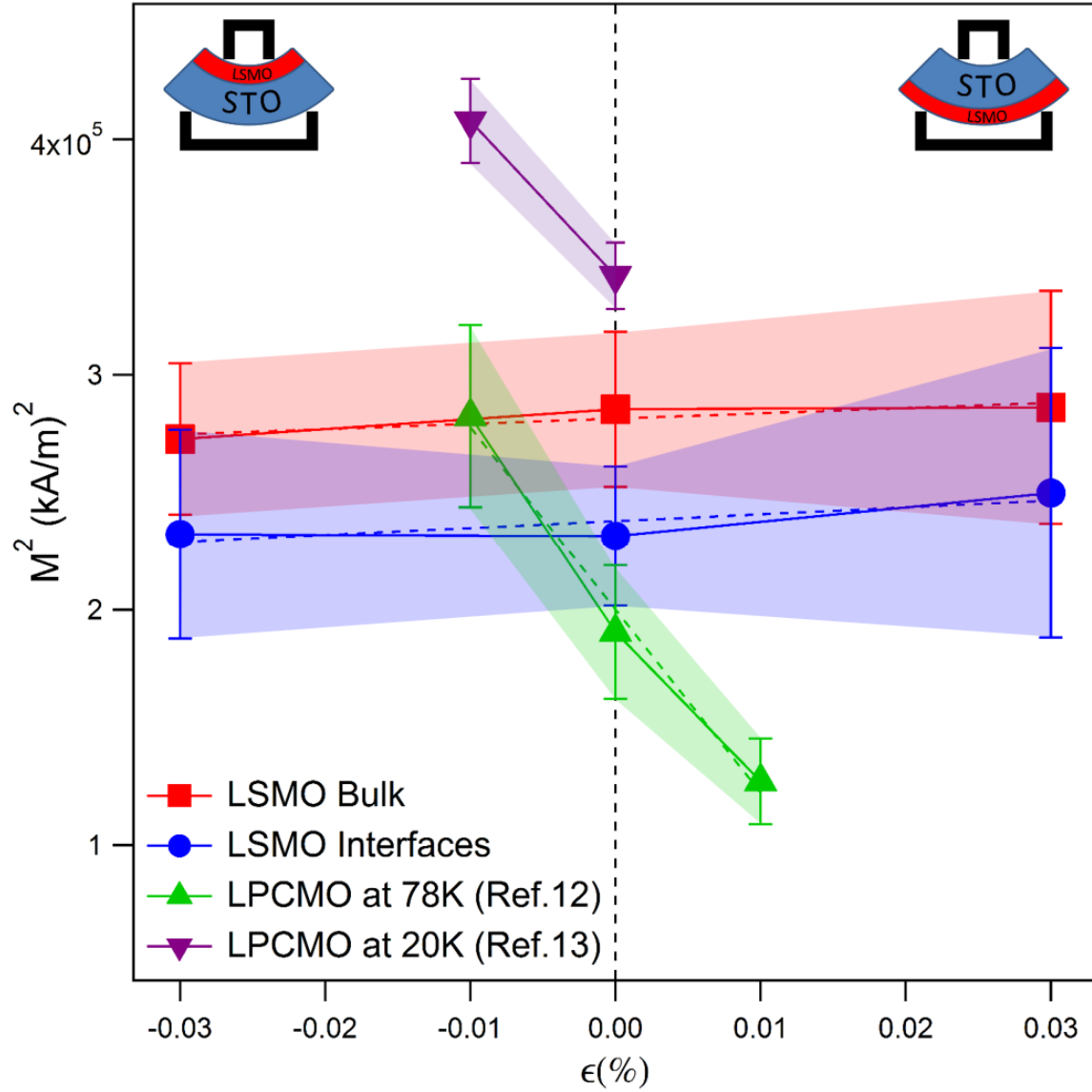


Figure 4. Square of the magnetization for the LSMO film bulk region (red), LSMO interfacial region (blue), LPCMO film bulk region at 78 K (green), and at 20 K (purple) vs. applied bending strain. The symbols represent the optimal values. The shaded regions represent the confidence of the values.

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